2812

orney Docket No. P19-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Satayadev Patel, et al.

Art Unit: 2812

Serial No.:

10/005,308

Examiner: Not Yet Assigned

Filed: December 3, 2001

For:

METHODS FOR DEPOSITING, RELEASING AND PACKAGING MICRO-

ELECTROMECHANICAL DEVICES ON WAFER SUBSTRATES

INFORMATION DISCLOSURE STATEMENT **PURSUANT TO 37 CFR 1.97(b)**

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-145

Sir:

The attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached PTO Form 1449. Copies of the cited references are enclosed.

No fee or certification is required in connection with this Information Disclosure Statement, since it is being submitted prior to the last of (1) issuance of a first official action on the merits and (2) expiration of the three month period following filing of the above-captioned application.

The above information is presented so that the Patent and Trademark Office can determine any materiality thereof to the claimed invention. It is respectfully requested that the information be considered during the prosecution of this application and that the cited documents be listed on the front page of any patent issuing from this application.

The Patent Office is authorized to charge our Deposit Account No. 501516 for any fee which it deems to be required to effect consideration of this statement.

Respectfully submitted,

Gregory R. Muir

Attorney for Applicant(s) Registration No. 35,293

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INFORMATION DISCLOSURE **CITATION**

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10/005,308

FILING DATE 12/03/01

APPLICANT Satayadev R. Patel, et al.

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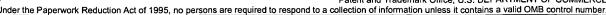
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APPLICANT Satayadev R. Patel, et al.

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Information Disclosure Statement- 2pgs PTO 1449 form citing references, copies of cited references Return Receipt Postcard Serial No.10/005,308, Attorney Docket No. P19-US

Dawn Roberts

This collection of information is required by 37 CFR 1.8. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 1.8 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.